

ABSTRACT

Disclosed are a photoetching apparatus and method. The photoetching apparatus comprises at least two sets of exposure devices and one set of substrate device, wherein the substrate device comprises a substrate stage (10) and a substrate (7), wherein the substrate stage (10) carries the substrate (7); and the at least two sets of exposure devices are symmetrically distributed, in the direction of exposure scanning, above the substrate (7), and form two exposure fields on the substrate (7) to expose the substrate (7) in the exposure fields.